## **Double gate MOSFET**

$$\phi_0 = 0.33347 V$$
  $\phi_0 = 0.33347 V$  SiO SiO SiO 0.5 nm 0.5 nm

$$\epsilon_{Si} = 11.7\epsilon_0$$
  
 $\epsilon_{SiO} = 3.9\epsilon_0$ 

Depletion approximation (Initial potential)

$$\rho = qN_{acc}$$

0.5 nm

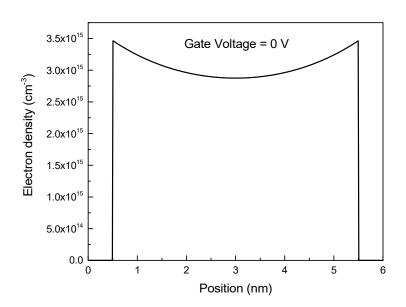
Including electron density (Updated potential)

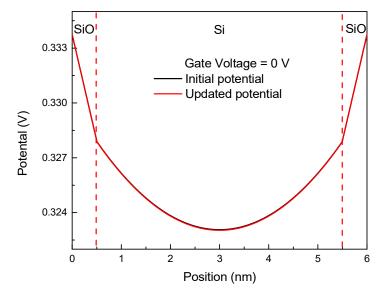
$$\rho = qN + qN_{acc}$$

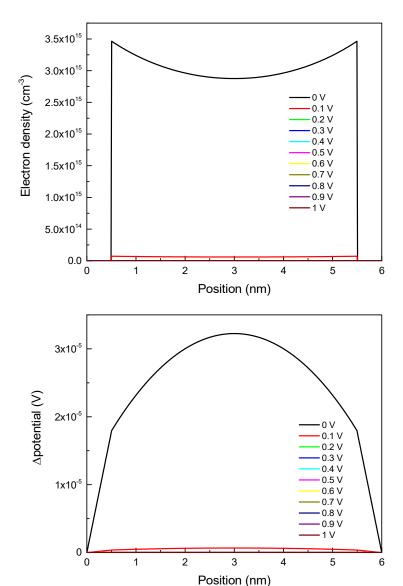
Electron density is small as much as negligible.

5 nm

- Depletion approximation is available in this case.







- Potential difference between initial and updated is dramatically reduced as gate voltage increases.
- Electron density is also dramatically reduced as gate voltage increases. This implies that current induced by drain-source voltage is reduced as the gate voltage increases. It is opposite to real system.
- This mismatched result is caused by the regardless of Schottky barrier.